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	APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
	10/663,081	09/16/2003	Hyun-Jae Kim	· YOM-0060	1689	
	23413	11/2/2004		EXAMINER		
		COLBURN, LLP ROAD SOUTH		MOHAMEDULLA, SALEHA R		
	BLOOMFIELD, CT 06002		,	ART UNIT	PAPER NUMBER	
				1756		
				DATE MAILED: 11/29/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)	\sim			
	10/663,081		11			
Office Action Summary	Examiner	KIM ET AL. Art Unit				
	Saleha R. Mohamedulla					
The MAILING DATE of this communication		the correspondence addr	ress			
Period for Reply						
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).						
Status						
1) Responsive to communication(s) filed of	on 27 Contombor 2004					
!	IN 27 September 2004. ☐ This action is non-final.					
		nrospolition as to the w	vita ia			
closed in accordance with the practice	3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims		1, 400 0.3. 210.				
	P = 0=					
4) Claim(s) <u>1-20</u> is/are pending in the app						
4a) Of the above claim(s) <u>14-20</u> is/are w 5) Claim(s) is/are allowed.	4a) Of the above claim(s) <u>14-20</u> is/are withdrawn from consideration.					
6)⊠ Claim(s) is/are allowed.						
7) Claim(s) <u>1-13</u> is/are rejected. 7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/or election requirement.						
Application Papers						
9) The specification is objected to by the Examiner.						
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.						
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) □ All b) □ Some * c) □ None of: 1. □ Certified copies of the priority documents have been received. 2. □ Certified copies of the priority documents have been received in Application No 3. □ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).						
* See the attached detailed Office action for a list of the certified copies not received.						
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Attachment(s)						
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-9) 	4) Interview Summ	nary (PTO-413)				
Notice of Draitsperson's Patent Drawing Review (PTO-9 Information Disclosure Statement(s) (PTO-1449 or PTO-9 Paper No(s)/Mail Date		il Date al Patent Application (PTO-152	2)			

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DETAILED ACTION

Election/Restriction

1. The Applicant's election of claims 1-13 on September 27, 2004 is acknowledged. Because the Applicant did not distinctly and specifically point out the supposed errors in the restriction requirement, the election has been treated as an election without traverse (MPEP § 818.03(a)). Claims 1-13 are considered and claims 14-20 are withdrawn from consideration.

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 2. Claims 1-13 are rejected under 35 U.S.C. 102(b) as being anticipated by US# 5,914,202 to Nguyen et al.
- 3. Nguyen teaches a mask and method of making and using the mask. A method is provided for forming a reticle on a reticle substrate, to transmit incident light. The method comprises the steps of depositing at least one film, to partially transmit incident light, over the reticle substrate, the partially transmitting film diminishing the intensity of light at predetermined percentage in transmission through the partially transmitting film, and the substrate passing substantially all light incident to the substrate. A method comprises the step of depositing an opaque film over the reticle substrate the opaque film blocking light so that

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substantially all incident light is attenuated. A method also comprises the step of etching selective portions of the opaque film deposited earlier, and the partially transmitted film deposited earlier, to reveal predetermined areas of reticle substrate and partially transmitting film, whereby light introduced to the reticle is transmitted through the predetermined areas of reticle substrate, partially transmitting film, and remaining opaque film to produce at least three intensities of light. Further, a method is provided for forming a photoresist profile on a substrate comprising the steps of providing a layer of photoresist having a predetermined thickness on the substrate, and directing light to the photoresist through a reticle having a first transmitting intensity to create a first exposure pattern in the photoresist, and the reticle having a second transmitting intensity to create a second exposure pattern in the photoresist. The method also including the step of developing the photoresist to remove a first thickness of photoresist, less than said predetermined thickness, in the areas of said first exposure pattern, and to remove a second thickness of the photoresist in the areas of the second exposure pattern, whereby the profile includes areas of photoresist having a plurality of different thicknesses (col. 4, line 55 - col. 5, line 20).

Conclusion

4. Any inquiry concerning this communication or earlier communications from the Examiner should be directed to Saleha Mohamedulla whose telephone number is (571) 272-1387. The Examiner can normally be reached Monday-Friday, from 8:00 AM to 4:30 PM.

If attempts to reach the Examiner by telephone are unsuccessful, the Examiner's supervisor, Mark Huff, can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Saleha R. Mohamedulla

Patent Examiner

Technology Center 1700

November 24, 2004